SHANTANU KALLAKURI

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EDUCATION.

Cornell University

Ithaca, NY

M.S. with Thesis in Materials Science and Engineering

Aug. 2018 - May 2021

- Advisors: Prof. Richard Robinson and Prof. Tobias Hanrath
- Thesis: 'Development of multiscale hierarchical structures from nanocluster mesophases' (10.7298/x221-2n24)
- Honors: Graduated with MS thesis, a co-op, patents, and a publication; CGPA: 3.84/4

Birla Institute of Technology & Science (BITS) Pilani

Pilani, India

Dual degree - B.E. in Chemical Engineering and M.Sc. in Chemistry

Aug. 2010 - Jul. 2015

- Advisor: Prof. Gokulnath Sabapathi, IICT (Indian Institute of Chemical Technology) (now at IISER-TVM)
- Thesis: 'Bi-conjugated Porphyrin and Sapphyrin macro-cycles for Dye-sensitized solar cells'
- Honors: Graduated with Honors in both degrees & Dept. rank 3 in Chemical engineering; Major GPA: 9.11/10

RESEARCH EXPERIENCE

Applied Materials Inc.

Santa Clara, CA

Senior Process Engineer, Atomic Layer Deposition Group, Semiconductor Products Group Aug. 2021 - Present

- Process owner for Olympia Applied's primary line of Plasma-enhanced atomic layer deposition (PE-ALD) machines developing process & chemistry for emergent Gate-all-around (GAA) transistors
- Spearheading a 7 member team to develop plasma-based conformal film deposition of dielectrics for fill & liner applications in advanced-node logic & memory GAA processes and their integration (n+2, sub-1.5nm & beyond)
- Executed multiple IP-protected projects in this role leading to multi-million dollar sales for Applied Materials product for various logic and memory customers. Filed 6 technology patents (Four granted, others pending)

Process Engineering Co-op (Mid-degree), Varian division, Applied Materials (MA)

Sept. 2019 – Sept. 2020

- Developed, executed, and patented plasma-enhanced deposition & etch processes for the two applications below. Honored with an *AMAT excellence award* for performance during the internship.
 - 1) Two plasma-enhanced chemical vapor deposition (PECVD) & one reactive-ion etch (RIE) processes to deposit and etch AR/VR waveguides using plasma gradient & grayscale methods for nanotopographic patterning and
 - 2) A PECVD processes for directional seeding and seam-free selective deposition of metal on Silicon and mixed Silicon substrates in Buried word-line (BWL) DRAM applications

Cornell University

Ithaca, NY

Graduate Thesis (Advisor: Prof. Richard Robinson), Materials Science & Engineering Aug. 2018 - May 2021

- Pioneered a one-pot synthesis of functional quantum dot magic-sized nanocrystals (MSNC) that hierarchically self-assemble into 99.9% pure, 6% monodisperse thin-films & fibers through a DNA-like biomimetic mesophase
- Developed and assembled novel chiral quantum dots using this system that are electrically and magnetically tunable. These dots are scalable across 7 orders of magnitude (nm-cm), support diverse chemical modifications, and can be easily analyzed using simple laser diffraction techniques. Published this research in *Nature Materials*

Brigham & Women's Hospital, Harvard-MIT HST

Cambridge, MA

Research assistant (Advisor: Prof. Hadi Shafiee), Engineering for medicine

Aug. 2016 - Feb. 2017

- Synthesized & surface-modified Janus Pt/Au nanomotors using Thiol cross-linking chemistry, Polymerase chain-reaction (PCR), Loop-mediated (LAMP) DNA amplification to spontaneously bind the nanomotors to pathogen DNA. Achieved 99% accurate HIV/Zika diagnosis by quantifying free vs bound motor velocity using a cellphone
- Published this research in ACS Nano & Nature Communications

Indian Institute of Chemical Technology

Hyderabad, India

UG Thesis (Advisor: Prof. Gokulnath Sabapathi), Polymers & Functional Materials

Jan. 2015 - Jul. 2015

- Designed and synthesized a light-harvesting push-pull expanded *Porphyrin* (*Sapphyrin*) and characterized it using electrochemical impedance spectroscopy (EIS) for Dye-sensitized solar cells (DSSC)
- Iterated through multiple pathways to successfully develop a high-yield solution based on *Thieno-pyrrole* (80%). The novelty was the donor-Pi bridge-acceptor dye which integrates usually disparate electronic regions
- Integrated the dye with a TiO_2 scaffold and Carbon, $Indium\ Tin\ Oxide\ (ITO)$ counter-electrode to build a working cell. Achieved the objective for a dye with broad Q, Soret bands to allow high-efficiency DSSC (10.3%)

CERTIFICATIONS_

Stanford: Harnessing the Power of AI/ML to Address New Engineering Challenges: Comprehensive 15-week course

SKILLS_

Advanced synthesis: nanoparticles - quantum-dots, spinel & core-shell nanoparticles; self-assembly - directed, hierarchical, amphiphilic; Thin-films & nanopatterning; Conjugated systems - donor-acceptor systems, conductive polymers, Porphyrins; Surface modification - Thio/Azo chemistry, ligand functionalization, trap-states Thin-film growth: PE-ALD, PE-CVD, ALE, selective deposition/etch, directional deposition/etch, RIE, SIMS Characterization: UV-Vis, XRD, NMR, FTIR, SAXS, OES, Ellipsometry, SRIM, EIS, Optical diffraction Simulation & modelling: LAMMPS, GAMESS (Basic), Blender, Cinema4D, Solidworks, AutoCAD, Ansys Fluent ML & AI: Convolutional neural networks, support vector regression, logistic & linear regression, kNNs, decision trees Programming: Python (proficient), Java (proficient), MatLab, C/C++, VBA, SQL, JavaScript, HTML/CSS Statistics: Pandas, NumPy, Scikit-learn, Tensorflow, SciPy, Seaborn, Matplotlib, SAS (JMP), DOE

SELECTED PUBLICATIONS & CONFERENCES.

AIx conference, Applied Materials (2024): "Detect or defect: A CNN-powered AI-driven approach to semiconductor defect classification" S. Kallakuri, Z. Zhang, R. Patil, L. Sun, M. Copic

Nature Materials, 21(5): 518-525 (2022): "Multiscale hierarchical structures from a nanocluster mesophase" H. Han, S. Kallakuri, Y. Yao, C. B. Williamson, D. R. Nevers, B. H. Savitzky, R. S. Skye, M. Xu, O. Voznyy, J. Dshemuchadse, L. F. Kourkoutis, S. J. Weinstein, T. Hanrath, R. D. Robinson

Nature Communications, 9(1): 4282 (2018): "DNA-engineered micromotors powered by metal nanoparticles for motion-based cellphone diagnostics" M. S. Draz, K. M. Kochehbyoki, A. Vasan, D. Battalapalli, A. Sreeram, M. K. Kanakasabapathy, S. Kallakuri, A. Tsibris, D. R. Kuritzkes, H. Shafiee

ACS Nano, 12(6): 5709-5718 (2018): "Motion-based immunological detection of Zika Virus using Pt-nanomotors and a cellphone" M. S. Draz, N. K. Lakshminaraasimulu, S. Krishnakumar, D. Battalapalli, A. Vasan, M. K. Kanakasabapathy, A. Sreeram, S. Kallakuri, P. Thirumalaraju, Y. Li, S. Hua, X. G. Yu, D. R. Kuritzkes, H. Shafiee

Functionalized engineering materials & their applications, 1(1):117-124 (2016): "Synthesis and characterization of templated Polyanilines: A new class of polymeric materials" J. Avusula, S. Kallakuri, S. Jayanty

SELECTED PATENTS.

US11956978B2 and US20240040808A1 | Techniques & devices using directional seeding & selective deposition (2024) M. Zeeshan, K. Chan, S. Kallakuri, S. Varghese. Two IPs describing selective, angular dielectric & metal deposition US11749564B2 | Techniques for void-free material depositions (2023)

M. Zeeshan, K. Chan, **S. Kallakuri**, S. Varghese, J. Hautala. This IP covers a foundational way to deposit metal in void-free manner for Buried Wordline (BWL) DRAM application in advanced transistors since voids raise resistance US11404314B2 | *Metal line patterning (2022)*

S. Varghese, M. Zeeshan, **S. Kallakuri**, K. Chan. This method describes a process-flow for selective fin patterning through deposition + etch using Plasma-enhanced CVD and/or ALD for transistor Wordline and Bitline application US20220100078A1 | Devices and methods for variable etch depths (Submitted, Pending)

M. Zeeshan, R. Bandy, P. Kurunczi, S. Kallakuri, T. Soldi, J. Olson. This IP covers a process-flow crucial to plasma etch process of waveguides and gratings on special glass (Various glass types) for augmented reality (AR) applications US20220119955A1 | Techniques for variable deposition profiles (Submitted, Pending)

M. Zeeshan, S. Kallakuri, J. Olson. This IP describes etch techniques to modulate refractive index for AR gratings

SCHOLASTIC ACHIEVEMENTS AND AWARDS_

(2020) Applied Materials internship excellence award & cash prize | (2014-2015) T.I.M.E undergraduate engineering & management scholarship | (2013-2015) BITS Pilani MCN (merit cum need) undergraduate scholarship | (2015) $Three\ Bronze$ and $Two\ Gold$ medals for university in Carrom and Soccer at national sports fests BOSM, SPREE, and ARENA | (2014) $Runner-up\ in\ National\ selection$ for Carom from Andhra Pradesh

TEACHING AND MENTORSHIP_

- Teaching assistant: (2020) MSE5860 Atomic structure, Prof. Richard Robinson | (2020) ENGRG1160 Intro to Engineering: Prof. Bruce Van Dover | (2018) MSE4330 Energy materials, Prof. Richard Robinson
- Mentored 4 batches of 7th-10th grade students as an Expanding your horizons (EYH) student engineering mentor
- Taught and mentored 32 undergraduates in Chemistry and Physics on Chegg/InstaEdu over the course of 3 years

LEADERSHIP & OUTREACH.

- Project coordinator, Asha: Raised over \$18000 in fund-raiser events (through concerts, workshops, and student-cooked dinners) for the non-profit, focused primarily on less privileged students in rural India
- Artist Liaison, Spicmacay: Organized 8 fund-raising concerts for the non-profit to help popularize Indian Carnatic & Hindustani music through artistes like Sikkil Gurucharan & Pt. Ronu Majumdar
- Community outreach lead, Yuva (Youth under visionary action) & Nirmaan: Organized over 6 summer education camps for 8th-10th grade students in Thimmapur & Dasarigudem villages focused on math and science education
- Event planner, Make a Difference (MAD): Regularly organize blood-donation drives (3+) & vaccine camps (2+)